

# Water Intensity Methodology

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## Our Approach

Water withdrawn intensity is calculated by dividing total water withdrawn for our manufacturing operations by fab production output. The Semiconductor Industry Association's standard normalization factor used to represent fab production output is squared centimeters of silicon multiplied by total mask layers. One mask layer represents one patterning step in semiconductor manufacturing. The greater the number of mask layers, the greater the number of processing steps necessary to manufacture the wafer. Emissions, energy usage, water usage, etc. generally scale with mask layers. They are also a function of the area, or size, of the wafer. It is therefore common practice to normalize resource usage by wafer area and number of mask layers in order to benchmark performance. The units for this metric are gallons / (cm<sup>2</sup> Si x # mask layers).